

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	7	drain and (conduct\$4 or metal) and (insulat\$4 or oxide) and gate and electrode and (implant near impur\$4) and channel and mask and wall and etch\$4 and pattern\$4 and wir\$4 and recess	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/27 12:14